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(54) Title: CRYSTALLINE-SI-LAYER-BEARING SUBSTRATE AND ITS PRODUCTION METHOD, AND CRYSTALLINE SI **DEVICE**

(57) Abstract: A method for producing a substrate having a crystalline Si layer comprising the steps of forming an amorphous Si layer on a plastic substrate, and irradiating the amorphous Si layer with a laser beam to crystallize the amorphous Si, wherein the plastic substrate has light transmittance of 30 to 100 % at an oscillation wavelength of the laser beam.